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Notice of Allowability	Application No.	Applicant(s)	
	09/994,279	CHIANG ET AL.	
	Examiner	Art Unit	
	David Nhu	2818	
The MAILING DATE of this communication ap All claims being allowable, PROSECUTION ON THE MERITS I herewith (or previously mailed), a Notice of Allowance (PTOL-8 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1.3	S (OR REMAINS) CLOSED 5) or other appropriate commercial RIGHTS. This application is	in this application. If not included nunication will be mailed in due cour	se. THIS
1. This communication is responsive to <u>5/8/05</u> .			
2. X The allowed claim(s) is/are 1-13,17,19 and 23-25.			
3. The drawings filed on <u>26 November 2001</u> are accepted l	by the Examiner.		
<ul> <li>4.</li></ul>	ve been received.		
2.   Certified copies of the priority documents ha	• •		
3.  Copies of the certified copies of the priority of	documents have been receiv	ed in this national stage application	from the
International Bureau (PCT Rule 17.2(a)).		· r	
* Certified copies not received:			
Applicant has THREE MONTHS FROM THE "MAILING DATE noted below. Failure to timely comply will result in ABANDON THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be substituted by the substitute of the substitute	NMENT of this application.		
INFORMAL PATENT APPLICATION (PTO-152) which g	ives reason(s) why the oath		
6. CORRECTED DRAWINGS (as "replacement sheets") m		/ DTO 040) - H 1	
(a) including changes required by the Notice of Draftspo		ew (P10-948) attached	
1)  hereto or 2)  to Paper No./Mail Date		ruin the Office action of	
(b) including changes required by the attached Examine Paper No./Mail Date	ers Amenament / Comment	or in the Office action of	
Identifying indicia such as the application number (see 37 CFF each sheet. Replacement sheet(s) should be labeled as such it			k) of
7. DEPOSIT OF and/or INFORMATION about the department attached Examiner's comment regarding REQUIREMEN			the
44	•		
Attachment(s) 1. ☑ Notice of References Cited (PTO-892)	5. ☐ Notice of	Informal Patent Application (PTO-15	2)
2. Notice of Draftperson's Patent Drawing Review (PTO-948	<del></del>	Summary (PTO-413),	
3. Information Disclosure Statements (PTO-1449 or PTO/SI Paper No./Mail Date		s Amendment/Comment	
4. Examiner's Comment Regarding Requirement for Deposit	t 8. 🗵 Examiner	s Statement of Reasons for Allowar	ce
of Biological Material	9. 🔲 Other	<del></del> .	
	X	wo I	

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## **EXAMINER'S AMENDMENT**

1. An examiner's amendment to the record appears below. Should the change and/or additions be unaceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

Claims 14-16, 18, 20-22 are cancelled.

## **REASONS FOR ALLOWANCE**

- 2. Claims 1-13, 17, 19, 23-25 are allowed.
- 3. The following is an examiner's statement of reasons for allowance: None of the references of record teaches or suggests as cited in claims 1, 17, 19: reacting said substrate with said modulated ions to remove any contaminants from said substrate and producing a modified substrate; introducing at least one additional ion generating feed gas into said evacuated chamber; generating a second plasma from said additional ion generating feed gas into said evacuated chamber; exposing said modified substrate to said additional ions; modulating said additional; reacting said adsorbed monolayer of said first reactant gas with said modulated additional ions to depend said thin film (as cited in claim 1); reacting said substrate with said radicals to remove any contaminants from said substrate and producing a modified substrate; introducing at least one additional radical generating feed gas into said evacuated chamber; generating a second plasma from said additional radical generating feed gas to form additional radicals; exposing said modified substrate to said additional radicals; reacting said adsorbed

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monolayer of said first reactant gas with said modulated additional radicals to depend said thin film (as cited in claims 17, 19);

4. Applicants filed an amendment on 5/10/05, and also filed at that time a terminal disclaimer statement with reference to USP: 6, 428, 859 B1.

5. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

## CONCLUSION

6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure: Chiang et al (6,428,858 B1): Sequential Method for Depositing A Film Modulated Ion-Induced Atomic Layer Deposition.

7. Any inquiry concerning this communication on earlier communications from the examiner should be directed to David Nhu, (703) 306-5796. The examiner can normally be reached on Monday-Friday from 7:30 AM to 5:00 PM.

The examiner's supervisor, David Nelms can be reached on (703) 308-4910.

The fax phone number for the organization where this application or proceeding is assigned is (703) 308-7382.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

David Nhu

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May 24, 2005

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introducing at least one additional radical generating feed gas into said evacuated chamber;

generating a second plasma from said additional radical generating feed gas to form additional radicals;

exposing said modified substrate to said additional radicals;

reacting said adsorbed monolayer of said first reactant gas with said additional radicals to deposit said thin film; and

repeating each of the aforementioned steps for each film deposition layer.

- 20. (cancelled)
- 21. (cancelled)

Cancelled

- 22. (withdrawn)
- 23. (previously presented) The sequential method of claim 1 wherein said additional radical generating feed gas is the same feed gas as said first radical generating feed gas.
- 24. (previously presented) The sequential method of claim 17 wherein said additional radical generating feed gas is the same feed gas as said first radical generating feed gas.
- 25. (previously presented) The sequential method of claim 19 wherein said additional radical generating feed gas is the same feed gas as said first radical generating feed gas.

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